



Fig. 1

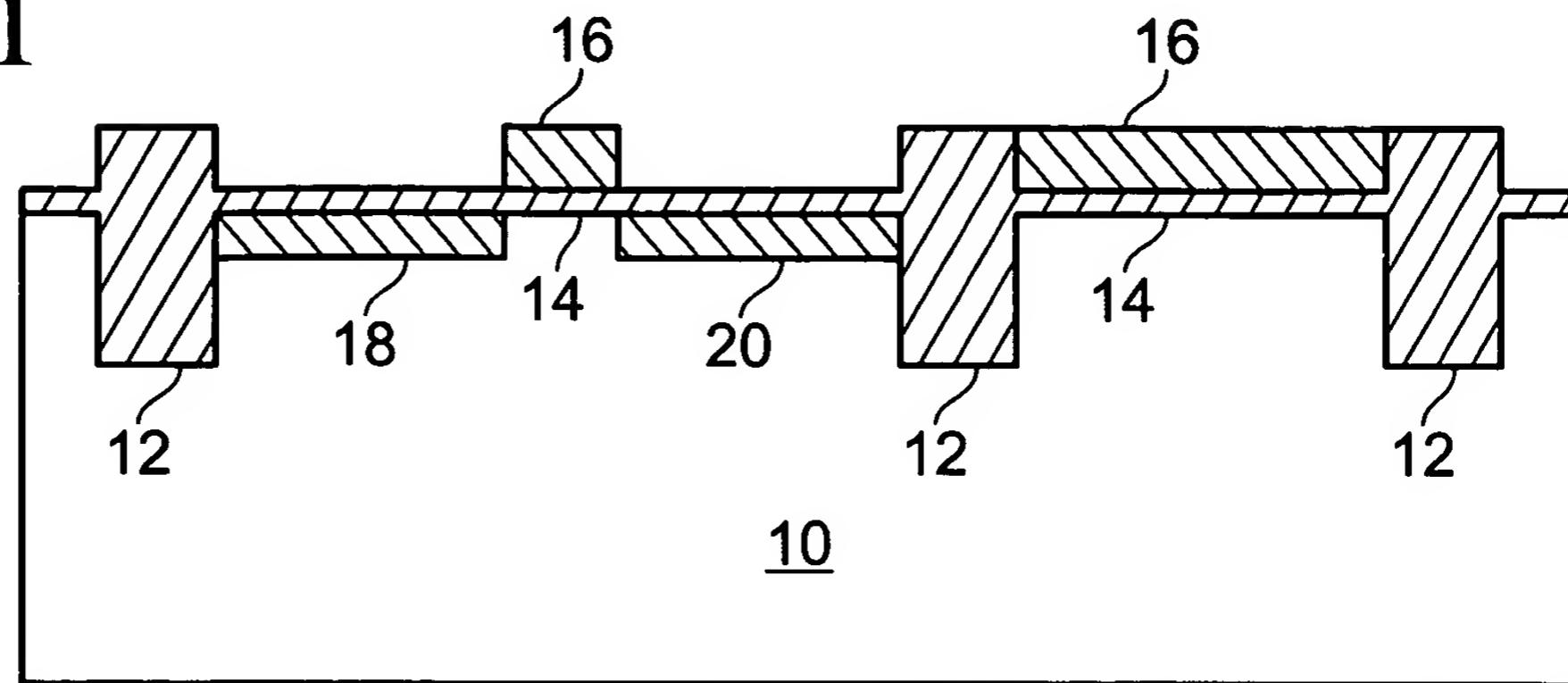


Fig. 2

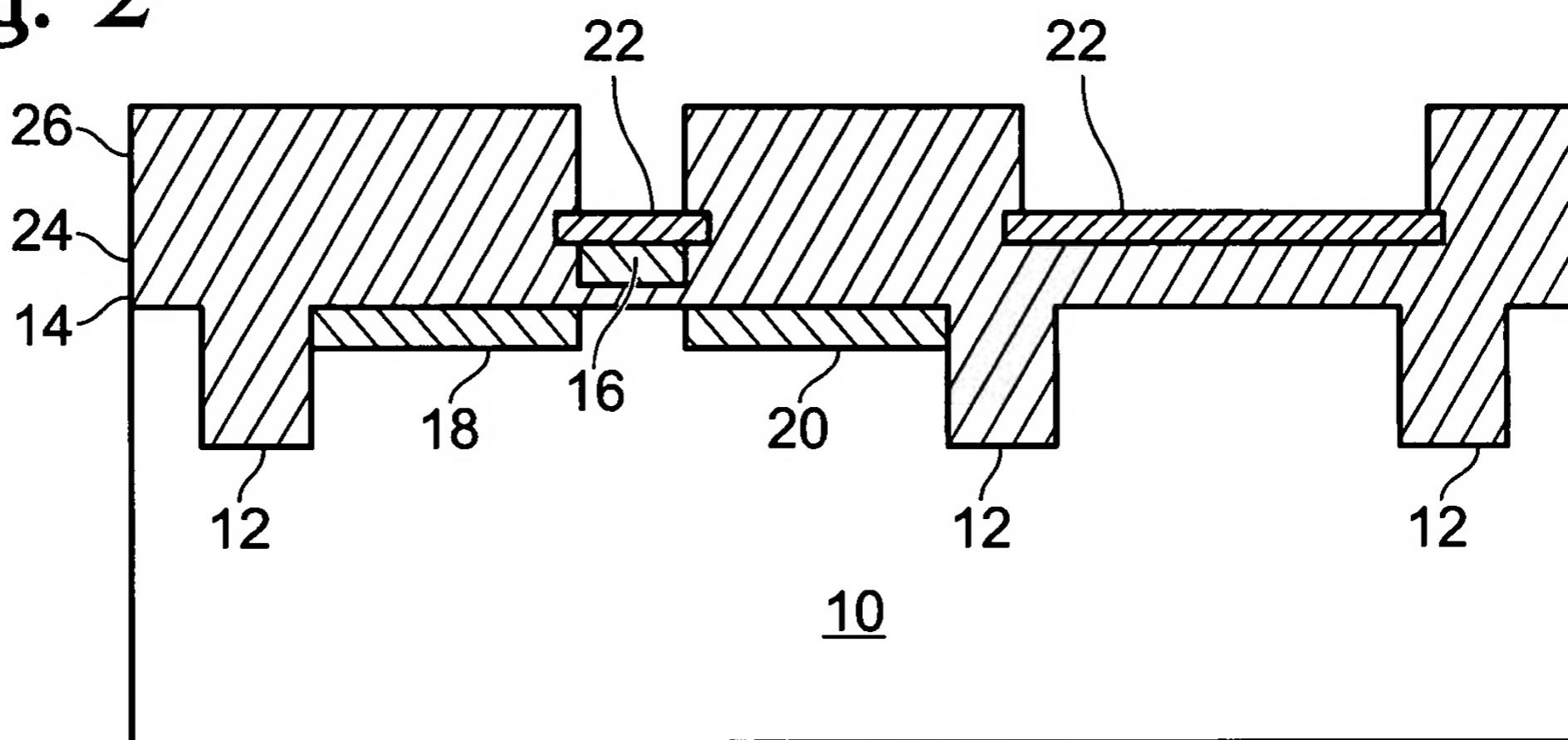


Fig. 3

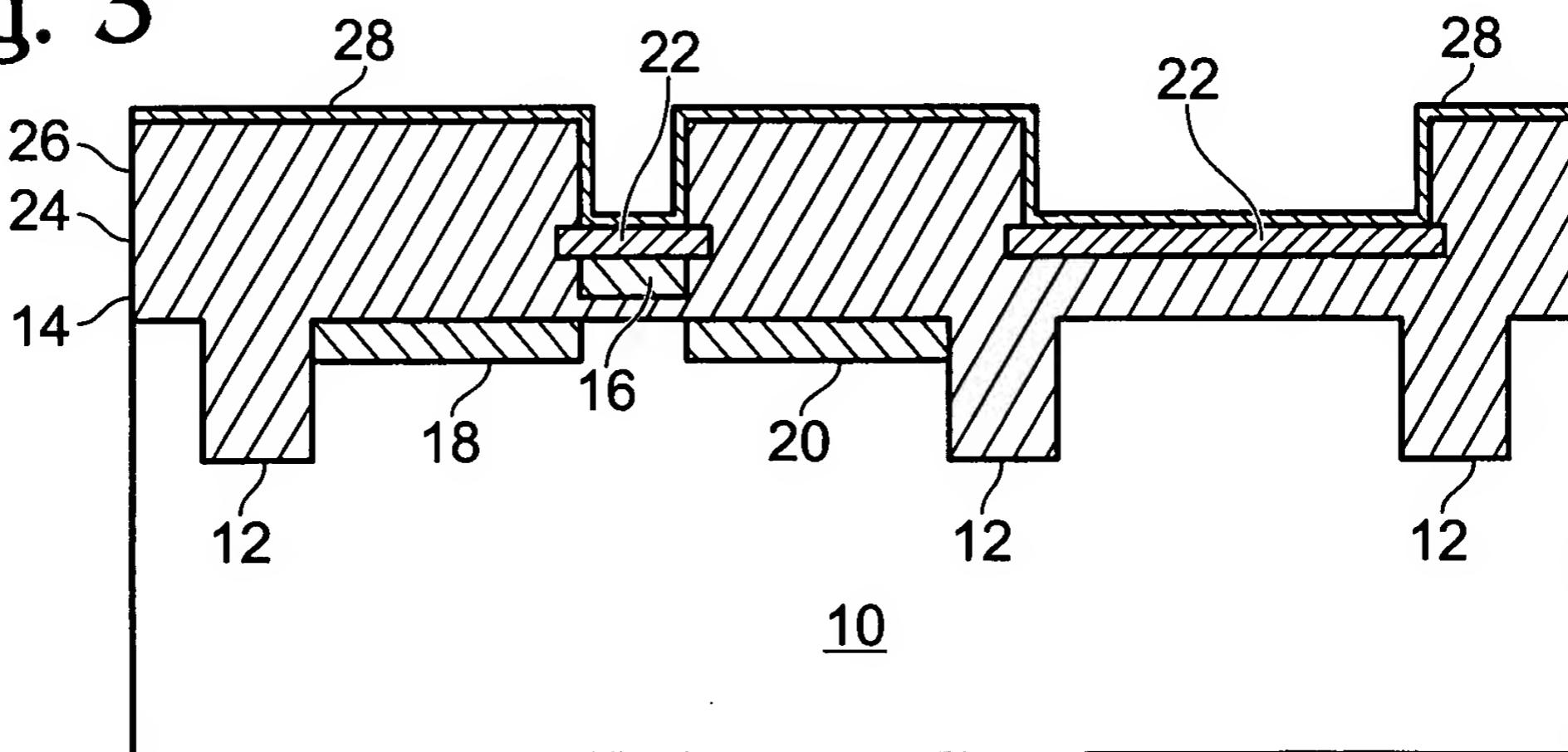




Fig. 4

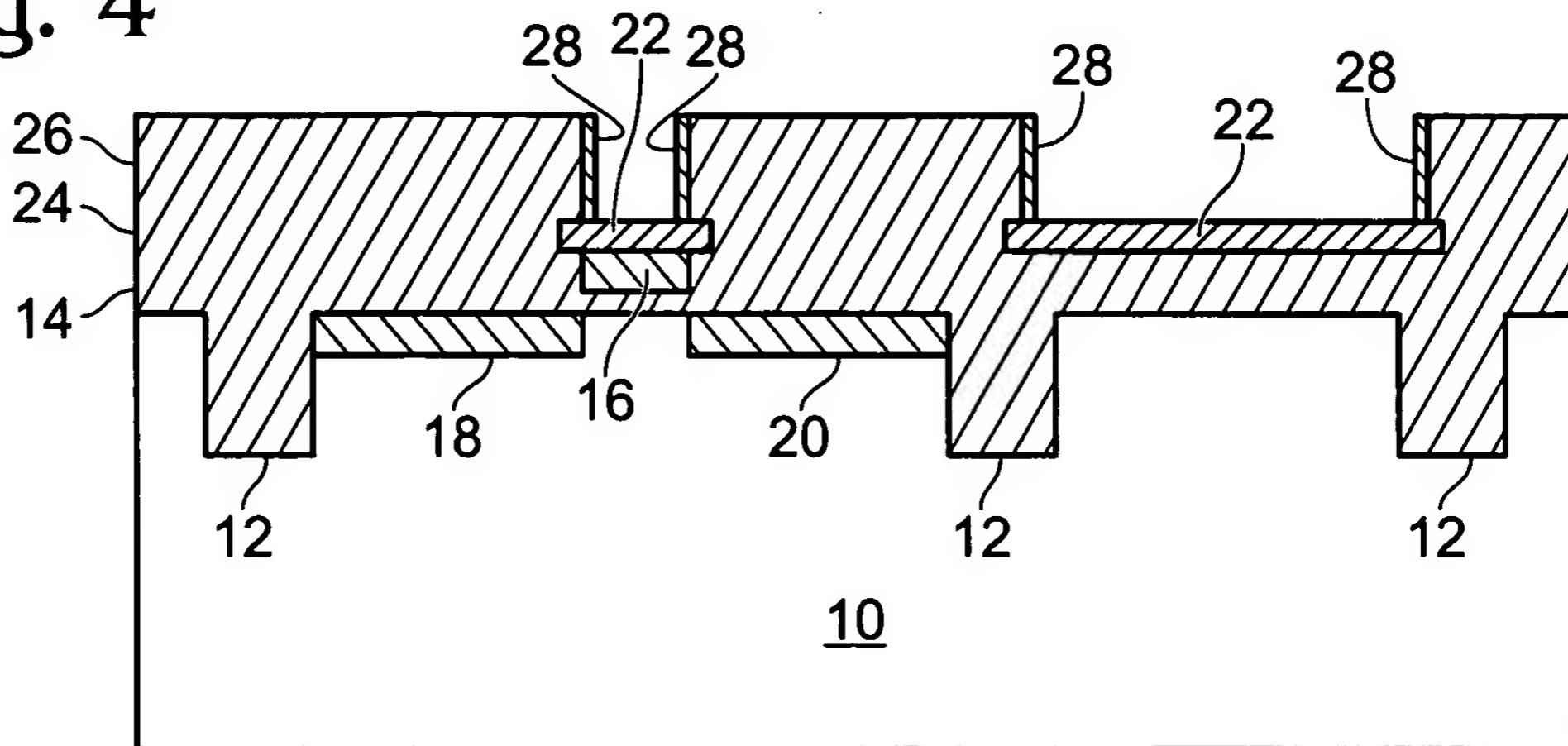


Fig. 5

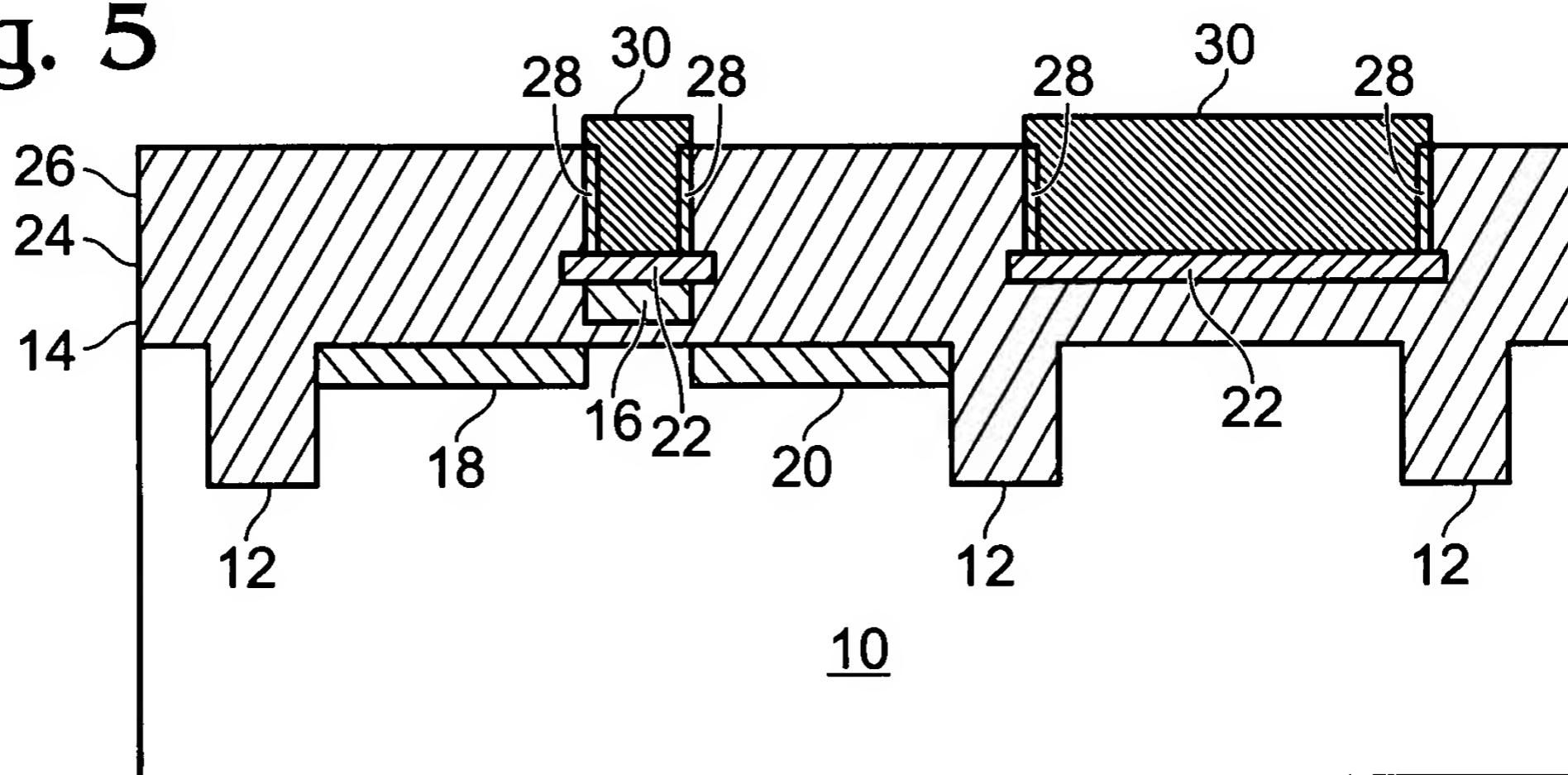


Fig. 6

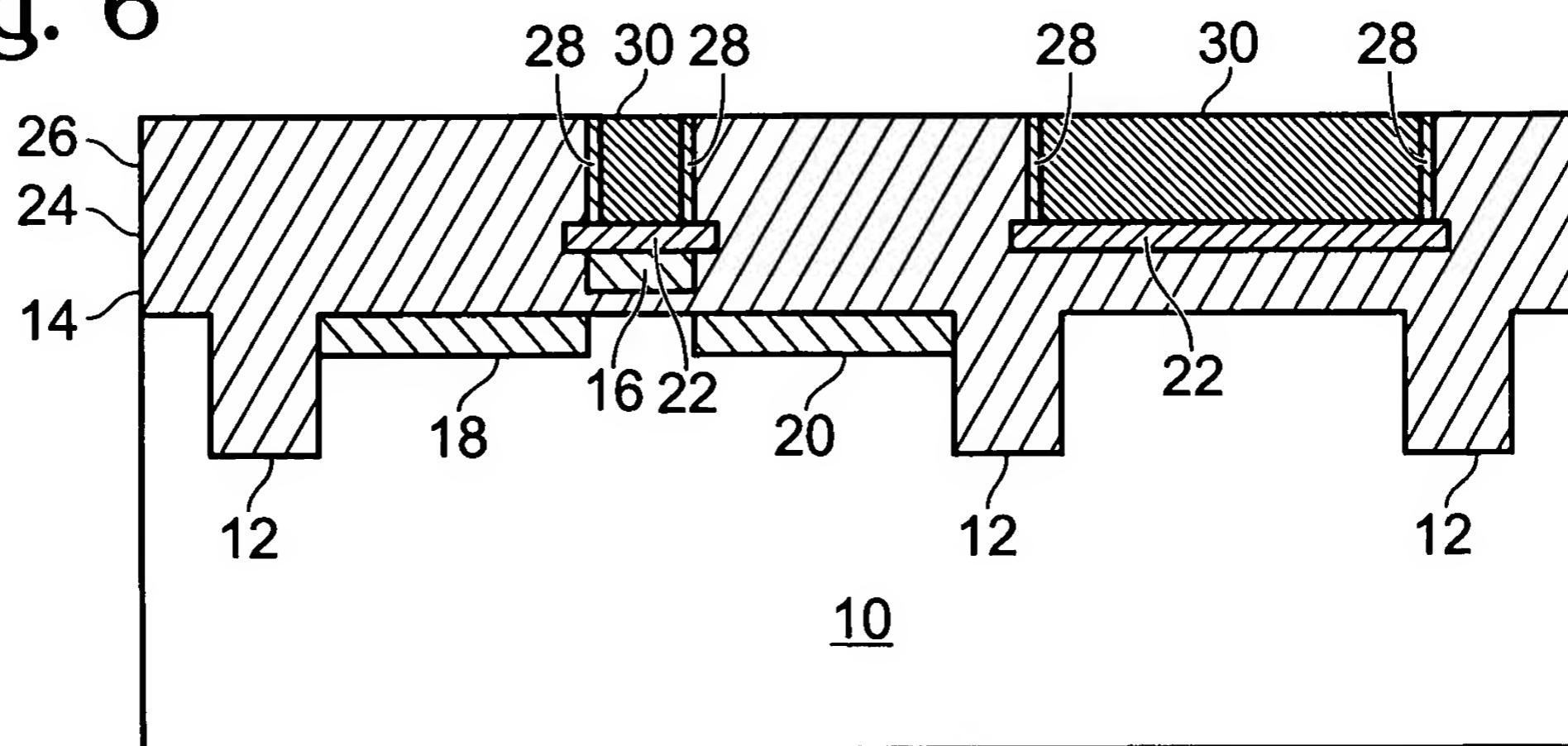




Fig. 7

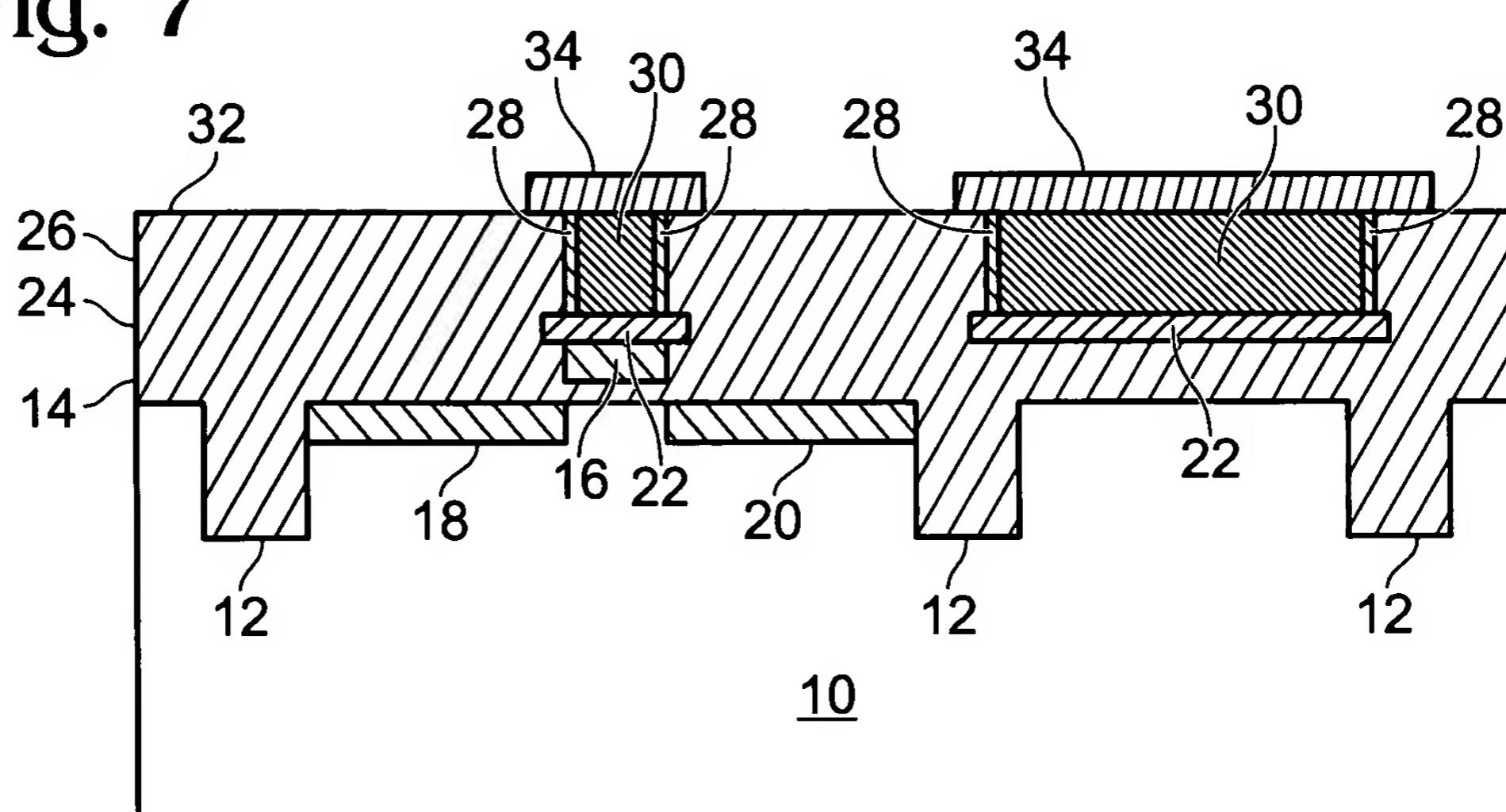
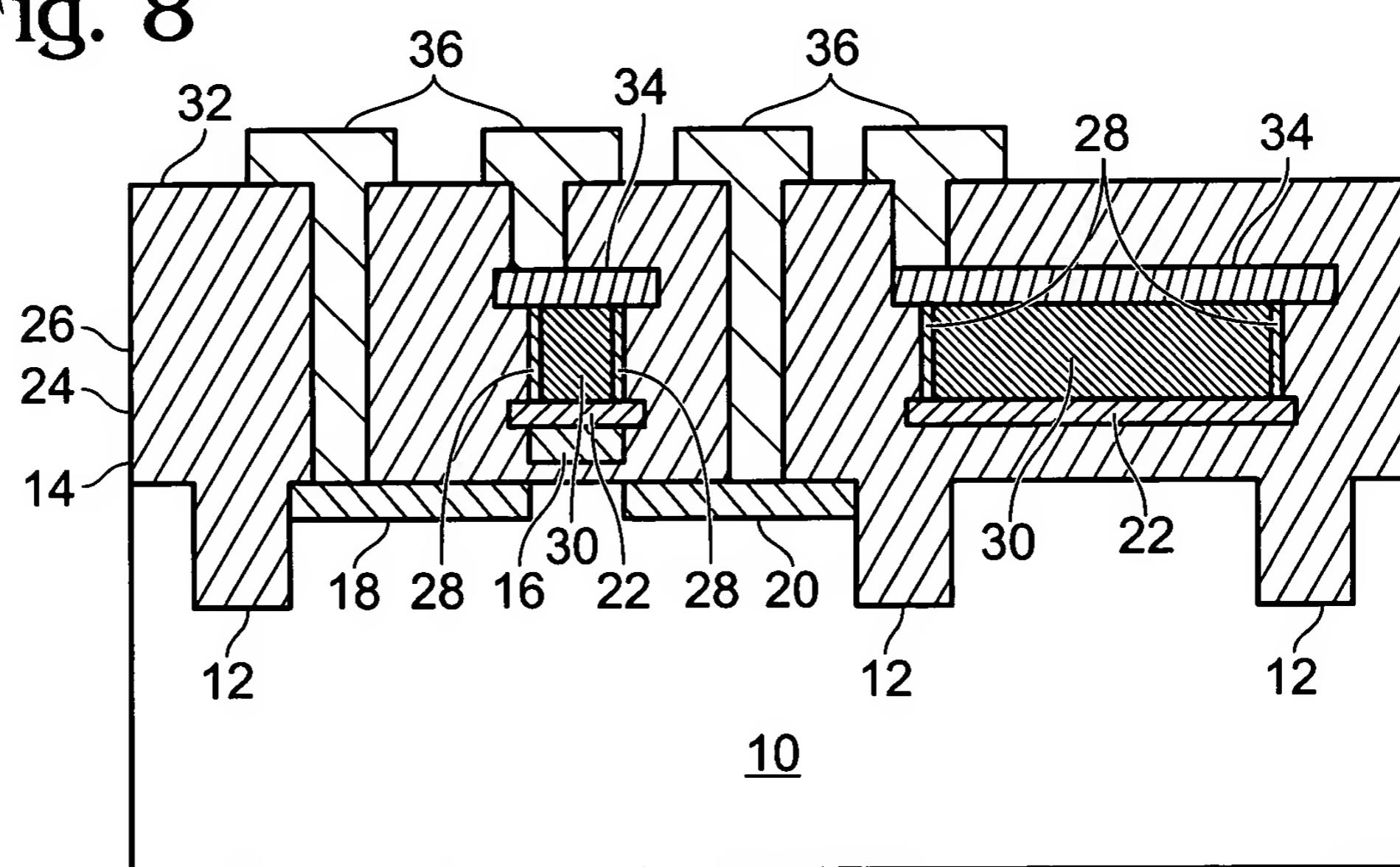


Fig. 8



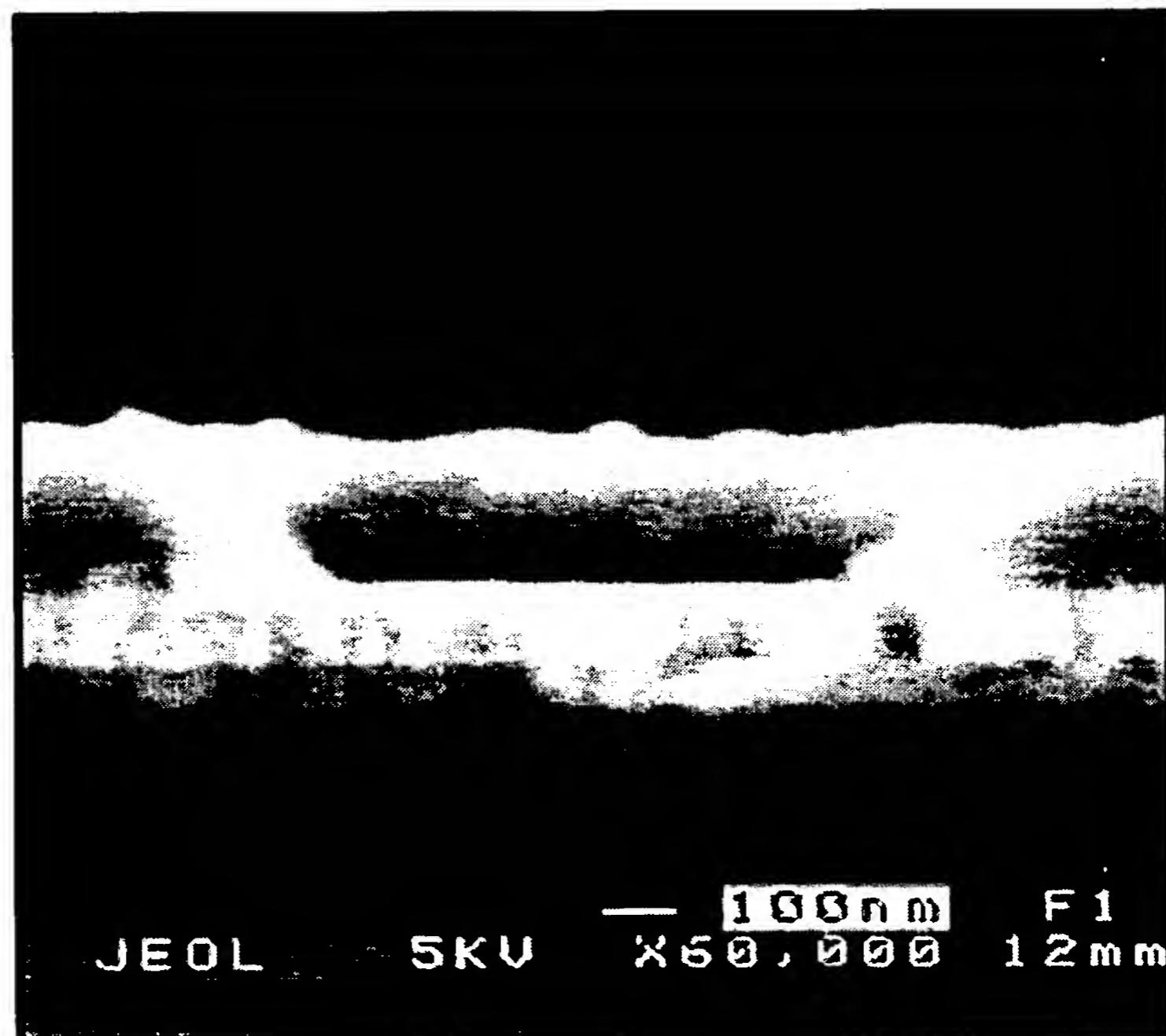


MOCVD of TiO<sub>2</sub> Thin Film for Use as FeRAM H<sub>2</sub> Passivation Layer  
Serial No.: 10/621,863  
Tingkai Li, Wei Pan, Robert A Barrowcliff, David R. Evans, and Shen Teng Hsu  
4/4

Fig. 9



Fig. 10



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